

# TEMPERATURE CONTROL SYSTEM FOR PLASMA PROCESSING APPARATUS

## ABSTRACT OF THE DISCLOSURE

5           A plasma processing system that includes a temperature management system  
and method that can achieve very accurate temperature control over a plasma  
processing apparatus is disclosed. In one embodiment, the temperature  
management system and method operate to achieve tight temperature control over  
surfaces of the plasma processing apparatus which interact with the plasma during  
10   fabrication of semiconductor devices. The tight temperature control offered by the  
invention can be implemented with combination heating and cooling blocks such  
that both heating and cooling can be provided from the same thermal interface.

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